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### **Press Contact**

Roger Halligan  
H+A International  
312.332.4650 ext. 22  
[rhalligan@h-a-intl.com](mailto:rhalligan@h-a-intl.com)

## **AIChE To Produce Multi-Faceted Conference Program For The 2011 CHEM SHOW In New York City**

*Pump Symposium, Valve Seminar, Nanotech Sessions Featured*

**WESTPORT, Connecticut...October 18, 2010** – AIChE (The American Institute of Chemical Engineers), the world's leading organization for chemical engineering professionals, is working closely with other industry-leading organizations to produce a unique, solutions-focused conference program for the 2011 CHEM SHOW in New York November 1-3.

The multi-faceted, two and a half day conference program from AIChE will feature the most popular elements of previous years, with new offerings on cutting-edge developments. Joe Cramer, AIChE's Technical Programming Director, said that the 2011 program is expected, for the first time, to include content from the Texas A&M Pump Symposium, as well as the continued involvement of the Valve Manufacturers Association (VMA) and nanotechnology sessions from iRAP (Innovative Research and Products). AIChE will develop a variety of sessions that will address today's critical topics, such as energy, and sustainability, as well as chemical engineering fundamentals, including mixing and separations.

“The conference program will be designed to provide processing professionals from around the world with insights on the latest trends and technologies they need to

run their operations more effectively,” said Cramer, “and will represent the most robust educational program ever offered at the CHEM SHOW.”

Based on the success of the first ever “AIChE Day” at the 2009 CHEM SHOW, the Show organizers asked AIChE if they would produce the entire conference program in 2011. A long-time supporter of the CHEM SHOW, AIChE saw this as an opportunity to reach out to other leading organizations and create a unique conference program that addresses various facets of the chemical processing industry.

The Texas A&M Pump Symposium is recognized around the world for its annual International Pump Users Symposium, which attracts thousands of pumping professionals to learn how to operate their equipment more efficiently. Many of the same topics addressed at the international meeting will be presented at the CHEM SHOW conference. The VMA will present the latest information on valves and actuators, in a format similar to the one used during the successful 2009 CHEM SHOW conference. iRAP will work closely with AIChE to keep processing professionals informed and updated on the latest advances in nanotechnology and how they relate to the processing industries.

Processing professionals attending the 2011 CHEM SHOW will have an unprecedented selection of sessions to choose from to help them do their jobs more effectively. Cramer stated that “attendees can learn about the latest technologies in the conference program and then see the actual equipment that makes it possible on the Show Floor.”

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### **About The CHEM SHOW**

Since 1915, the CHEM SHOW has been the CPI professional’s single best resource for new products, new ideas and new services. It’s a hands-on, interactive event that showcases a wide spectrum of emerging technologies. The unique industry forum creates a dynamic marketing environment unequaled by any other process industries event in North America. The CHEM SHOW is produced and managed by International Exposition Company (IEC), 15 Franklin Street, Westport, CT 06880; phone: (203) 221-9232; fax: (203) 221-9260; e-mail: [info@chemshow.com](mailto:info@chemshow.com); website: [www.chemshow.com](http://www.chemshow.com).

## About AIChE

AIChE, founded in 1908, is a professional association of 40,000 chemical engineers in 92 countries. Its members work in corporations, universities and government using their knowledge of chemical processes to develop safe and useful products for the benefit of society. For more information, please go to [www.aiche.org](http://www.aiche.org).